

ATTY. DOCKET NO.
RD-28,667SERIAL NO.
09/683,149INFORMATION DISCLOSURE STATEMENT BY APPLICANT
LIST OF ITEMSApplicant
Marc (NMN) SchaepkensFiling Date
11/27/2001

Group

U.S. PATENT DOCUMENTS

*EXAMINER INITIAL	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
<i>DSM</i>	A1 4,871,580	10/3/89	Schram et al.			
	A2 4,957,062	9/18/90	Schuurmans et al.			
	A3 5,120,568	6/9/92	Schuurmans et al.			
	A4 6,213,049	4/10/01	Yang			
	A5					

FOREIGN PATENT DOCUMENTS

	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION YES NO
	B1					
	B2					

OTHER INFORMATION (Including Author, Title, Date, Pertinent Pages, etc.)

<i>DSM</i>	C1	"Temperature and Growth-Rate Effects on the Hydrogen Incorporation in Hydrogenated Amorphous Silicon", WMM Kessels et al., Department of Applied Physics, Eindhoven University of Technology, 1998, pp 29-33.
<i>DSM</i>	C2	"Improvement of Hydrogenated Amorphous Silicon Properties With Increasing Contribution of SiH ₄ to Film Growth", WMM Kessels et al., Department of Applied Physics, Eindhoven University of Technology, pp 107-110.
	C3	Application Serial No. 09/681,820, filed June 11, 2001, "Apparatus and Method for Large Area Chemical Vapor Deposition Using Multiple Expanding thermal Plasma Generators".
	C4	Specification RD-28,484 - "Apparatus and Method for Depositing Large Area Coatings on Non-Planar Surfaces", Marc (NMN) Schaepkens 09/683,148
	C5	
	C6	
	C7	
	C8	

EXAMINER

Alexander

DATE CONSIDERED

11/27/04

EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant